## EE 330

## Homework 2 Solutions Fall 2024

1)

DRC stands for Design Rule Checking and ensures that all the dimensional tolerances involved within a given process are followed within a layout. For example, if two metal1 interconnects are placed too close to each other, DRC would find that the two interconnects are less than minimally spaced. This tool does not check that correct connections are made, just that the layout meets dimensional rules and manufacturing tolerances.

LVS stands for Layout VS Schematic and ensures that all electrical connections made within a given layout are identical to electrical connections made within a given schematic. For example, if an NMOS gate is tied to an input A in the layout but is tied to an input B within the schematic, the LVS tool would find that the NMOS gate is tied to a different input between the schematic and the layout. This tool does not check that any dimensional rules or manufacturing tolerances are met, just that connections between the layout and schematic are correct.

2)

Wafer area =  $\pi r^2 = \pi (22.5 cm)^2 = 1590.43 cm^2$ 

Dies/Wafer (ignoring edge cases) =  $\frac{1590.43cm^2}{0.5cm^2}$  = 3180.86 ~ 3180 $\frac{dies}{wafer}$ Ideal cost per die =  $\frac{$3000}{3180 \ dies}$  = \$0.94 Yield =  $\frac{Ideal \ cost \ per \ die}{Cost \ per \ die}$  =  $\frac{$0.94}{$3.00}$  = 31.33%

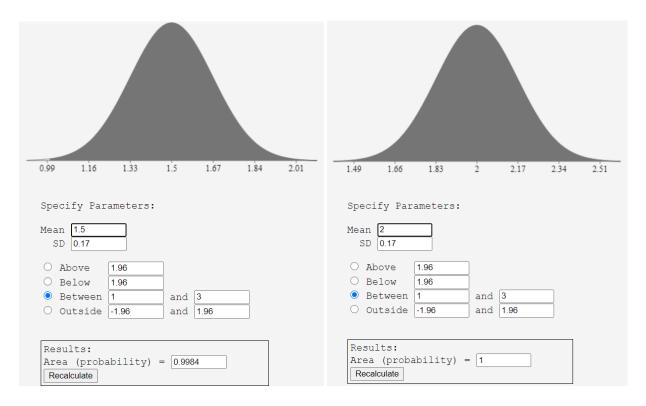
3)

Die area = 
$$(side \ length)^2 = (6mm)^2 = (0.6cm)^2 = 0.36cm^2$$
  
Hard yield =  $Y_H = e^{-Ad} = e^{-(0.36cm^2)(0.8cm^{-2})} = 74.98\%$   
Total yield =  $Y = Y_H Y_S = (74.98\%)(100\%) = 74.98\%$   
Dies/wafer (ignoring edge cases) =  $\frac{Wafer \ area}{Die \ area} = \frac{\pi(150mm)^2}{(6mm)^2} = 1962.5 \sim 1963 \ dies/wafer$   
Good Dies/wafer =  $(1963 \ dies \ wafer) * (.7498) = 1472 \ good \ dies/wafer$   
Cost per good die =  $\frac{Cost \ per \ wafer}{number \ of \ good \ dies} = \frac{\$3200}{1472 \ dies} = \$2.17$ 

4)

Using a normal distribution calculator

https://onlinestatbook.com/2/calculators/normal\_dist.html



5)

14nm transistor gate area =  $(14nm)^2 = 196nm^2$ 

14nm transistor total area =  $area * overhead = area * 10 = 1960nm^2 = 1.96 * 10^{-11} cm^2$ 

Transistors per die = 
$$\frac{Die Area}{Transistor Area} = \frac{0.25cm^2}{1.96*10^{-11}cm^2} = 1.276*10^{10} \frac{transistors}{die}$$

New transistor area =  $(3nm)^2 * overhead = 9nm^2 * 10 = 90nm^2$ 

New die area = 
$$\frac{transistors}{die} * transistor area = 1.276 * 10^{10} * 90nm^2 = 1.148mm^2$$

New dies/wafer (ignoring edge cases) =  $\frac{Wafer Area}{Die area} = \frac{\pi (225mm)^2}{1.148mm^2} = 138539 dies$ 

6)

a) Expected hard yield =  $Y_H = e^{-Ad} = e^{-(0.85mm^2)(1cm^{-2})} = e^{-(0.0085cm^2)(1cm^{-2})}$ 

 $Y_H = e^{-0.0085} = 0.9915 = 99.15\%$ 

b) Expected overall yield =  $Y_{overall} = Y_H Y_S = (0.9915)(0.99)$ 

 $Y_{overall} = 0.9815 = 98.15\%$ 

c) As spec'd, this ADC is suitable to be produced at the fab location, as expected overall yield is greater than the 95% yield limit. To find maximum allowable ADC area to stay within 95% yield limit, derive an equation relating ADC area to yield, with  $Y_{overall} = 0.95$ .

$$Y_{overall} = Y_S Y_H = Y_S e^{-(die \, area \, cm^2)(1cm^{-2})}$$

die area 
$$cm^2 = \frac{\ln\left(\frac{Y_{overall}}{Y_S}\right)}{-1cm^{-2}} = \frac{-0.04124}{-1cm^2} = 0.04124cm^2 = 4.124mm^2$$

7)

Probability that one operational amplifier meets the offset voltage criteria

$$\mu = 0V, \sigma = 3mV$$

$$P(1 \text{ Good op amp}) = \left(2 * F_N \left(\frac{5mV - 0mV}{3mV}\right) - 1\right)$$

$$P(1 \text{ Good op amp}) = \left(2 * F_N(1.66)\right) - 1$$

$$P(1 \text{ Good op amp}) = (2 * .9515) - 1 = 1.903 - 1 = 0.903$$

Probability that both operational amplifiers meet the offset voltage criteria

$$P(2 Good op amps) = P(1 Good op amp) * P(1 Good op amp)$$

P(2 Good op amps) = 0.903 \* 0.903 = 0.8154

The probability that there is an IC with both operational amplifiers meeting the offset voltage requirements with the given standard deviation and mean is 0.8154. This gives us a soft yield of 81.54%.

8)

/\*implementation of HW 2 problem 8

2 specified gates included in code

switch between code with en input

en=0 -> 3-in nor

en=1 -> 2-in nand, doesnt use C

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`timescale 1ns/1ps

//give us a nice timescale for simulation

module hw2q8(A, B, C, En, F);	<pre>//instantiate the module</pre>
input A, B, C, En;	//define inputs
output F;	//define output
reg Out;	//define placeholder reg for use in always block
assign F = Out;	//assign placeholder reg to output
always @ (A or B or C or En) begin	//any time an input changes

if (!En) begin	//if enable is ze	ro
Out = ~(A  B  C);	//F=!(A+B+C)	
end	//exit if stateme	ent
if (En) begin	//if enable is on	e
Out = ~(A&B);	//F = !(A&B)	
end	//exit if stateme	ent
end	//exit a	ways statement
endmodule		//end of module
/*standard 4-input logic testbench		
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`timescale 1ns/1ps		<pre>//set timescale to something nice to simulate</pre>
module standard_tb();		//instantiate testbench module
reg a,b,c,en;		//define input registers
wire out;		//define output wire
hw2q8 DUT(.A(a), .B(b),	.C(c), .En(en), .F(out));	//instantiate Device Under Test
initial a = 0;	//set in	itial input values
initial b = 0;		
initial c = 0;		
initial en = 0;		
always #1 a = ~a;	//for input n, toggle every 2^n time units	
always #2 b = ~b;		
always #4 c = ~c;		
always #8 en = ~en;		

